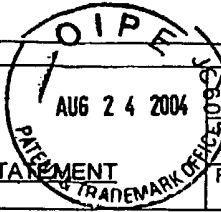


FORM PTO-1449				Page 1 of 3			
<div style="display: flex; justify-content: space-between; align-items: center;"> <div> <p>INFORMATION DISCLOSURE STATEMENT</p> <p>U.S. PATENT DOCUMENTS</p> </div> <div style="text-align: right;"> <p>ATTY. DOCKET NO. 1857.1670001</p> <p>APPLICATION NO. 10/781,803</p> </div> </div>				<p>FIRST NAMED INVENTOR Nabila Baba-Ali</p>			
				<p>FILING DATE February 2, 2004</p> <p>ART UNIT 1752</p>			
U.S. PATENT DOCUMENTS							
EXAMINER INITIAL		DOCUMENT NUMBER	DATE	NAME	CLASS	SUB-CLASS	FILING DATE
ND	AA1	5,537,260	07/16/1996	Williamson	359	727	_____
ND	AB1	5,442,184	08/15/1995	Palmer et al.	250	492.2	_____
ND	AC1	6,108,140	08/22/2000	Hashimoto et al.	359	727	_____
ND	AD1	5,144,362	09/01/1992	Kamon et al.	355	53	_____
ND	AE1	6,229,647 B1	05/08/2001	Takahashi et al.	359	487	_____
ND	AF1	3,917,399	11/04/1975	Buzawa et al.	355	43	_____
ND	AG1	5,436,761	07/25/1995	Kamon	359	487	_____
	AH1						
	AI1						
	AJ1						
	AK1						
FOREIGN PATENT DOCUMENTS							
EXAMINER INITIAL		DOCUMENT NUMBER	DATE	COUNTRY	CLASS	SUB-CLASS	TRANSLATION
ND	AL1	EP 1 091 252 A2	04/11/2001	Europe			X Yes No
ND	AM1	WO 01/22164 A1	03/29/2001	WIPO			Yes X No
	AN1						Yes No
	AO1						Yes No
	AP1						Yes No
OTHER (Including Author, Title, Date, Pertinent Pages, etc.)							
ND	AR	1	"Understanding the Forbidden Pitch Phenomenon and Assist Feature Placement," Shi et al., SPIE Vol. 4689: 985-996 (2002).				
ND	AS	1	"Forbidden Pitches for 130nm Lithography and Below," Socha et al., SPIE Vol. 4000: 1140-1155 (2000).				
ND	AT	1	A. K. Wong, <u>Resolution Enhancement Techniques in Optical Lithography</u> , SPIE Press, pages 28-29				
EXAMINER <i>Dorothy Chacko Davis</i>					DATE CONSIDERED		
					09/24/2004		
<p>EXAMINER: Initial if reference considered, whether or not citation is in conformance with MPEP 609. Draw line through citation if not in conformance and not considered. Include copy of this form with next communication to Applicant.</p>							

FORM PTO-1449 INFORMATION DISCLOSURE STATEMENT			ATTORNEY DOCKET NO. 1857.1670001	APPLICATION NO. 10/781,803
			FIRST NAMED INVENTOR Nabila Baba-Ali	
			FILING DATE February 2, 2004	ART UNIT 1752

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U.S. PATENT DOCUMENTS							
EXAMINER INITIAL		DOCUMENT NUMBER	DATE	NAME	CLASS	SUB-CLASS	FILING DATE
	AA2						
	AB2						
	AC2						
	AD2						
	AE2						
	AF2						
	AG2						
	AH2						
	AI2						
	AJ2						
	AK2						

FOREIGN PATENT DOCUMENTS							
EXAMINER INITIAL		DOCUMENT NUMBER	DATE	COUNTRY	CLASS	SUB-CLASS	TRANSLATION
	AL2						Yes
							No
	AM2						Yes
							No
	AN2						Yes
							No
	AO2						Yes
							No
	AP2						Yes
							No

OTHER (Including Author, Title, Date, Pertinent Pages, etc.)			
DLD	AR	2	"Impact of Illumination Coherence and Polarization on the Imaging of Attenuated Phase Shift Masks," Ma et al., SPIE Vol. 4346: 1522-1532 (2001).
DLD	AS	2	"Solutions for Printing Sub 100nm Contacts with ArF," Graupner et al., SPIE Vol. 4691: 503-514 (2002).
DLD	AT	2	"The Vortex Via Mask: Making 80nm Contacts With a Twist!," Levenson et al., SPIE Vol. 4889 (2002).

EXAMINER <i>Barth Charles Davis</i>	DATE CONSIDERED <i>09/24/2004</i>
EXAMINER: Initial if reference considered, whether or not citation is in conformance with MPEP 609. Draw line through citation if not in conformance and not considered. Include copy of this form with next communication to Applicant.	

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INFORMATION DISCLOSURE STATEMENT

ATTY. DOCKET NO.
1857.1670001APPLICATION NO.
10/781,803FIRST NAMED INVENTOR
Nabila Baba-AliFILING DATE
February 2, 2004ART UNIT
1752

U.S. PATENT DOCUMENTS

EXAMINER INITIAL		DOCUMENT NUMBER	DATE	NAME	CLASS	SUB-CLASS	FILING DATE
	AA3						
	AB3						
	AC3						
	AD3						
	AE3						
	AF3						
	AG3						
	AH3						
	AI3						
	AJ3						
	AK3						

FOREIGN PATENT DOCUMENTS

EXAMINER INITIAL		DOCUMENT NUMBER	DATE	COUNTRY	CLASS	SUB-CLASS	TRANSLATION
	AL3						Yes No
	AM3						Yes No
	AN3						Yes No
	AO3						Yes No
	AP3						Yes No

OTHER (Including Author, Title, Date, Pertinent Pages, etc.)

<i>DND</i>	AR	<u>3</u>	"Overcoming the Resolution Challenge Using Special Illumination Techniques to Print 50/50 nm Nested Contact Holes at 157 nm Wavelength," Baba-Ali et al., SPIE Vol. 5040: 1352-1363 (2003).				
	AS	<u>3</u>					
	AT	<u>3</u>					

EXAMINER *Daniel Charles Davis*DATE CONSIDERED *09/24/2004*

EXAMINER: Initial if reference considered, whether or not citation is in conformance with MPEP 609. Draw line through citation if not in conformance and not considered. Include copy of this form with next communication to Applicant.